



520.35833VV5

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): KAZUMI, et al.

RECEIVED

Serial No.: 10/086,710

APR 22 2003

Filed: March 4, 2002

GROUP 1700

For: PLASMA PROCESSING APPARATUS

Group: 1763

Examiner: Hassanzadeh

AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

April 14, 2003

#8B
4/28/03
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Sir:

In response to the Office Action of November 14, 2002, please amend the above-identified application as follows:

IN THE SPECIFICATION

Please replace the paragraph beginning on page 2, line 8 with the following replacement paragraph:

The plasma density distribution is determined mainly by the generation rate distribution and by the state of transportation of ions and electrons. In the absence of an external magnetic field, the transportation of the plasma diffuses isotropically in every direction. At this time, electrons instantly escape and tend to reach the wall of the vacuum chamber because the mass is no more than 1/1,000 of that of an ion, but they are repelled by the sheath (ion sheath) formed in the vicinity of the wall. As a result, a quasi-neutral condition of the electron and ion densities is always met in

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